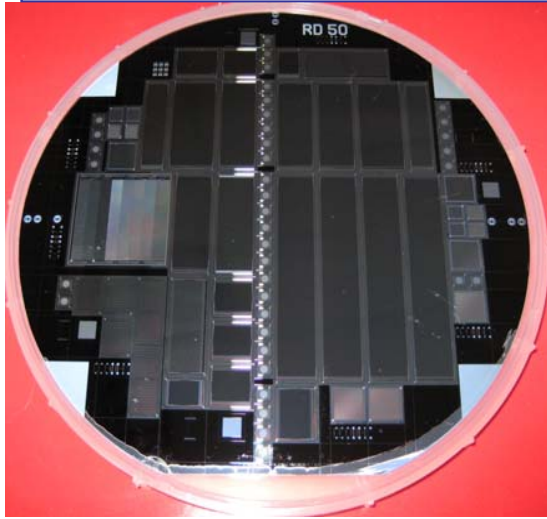


Status of Common RD50 6" Fab. with Micron



	MCz (n-p)	MCz(n-n), (p-n)	Fz (n-p)	Fz (n-n), (p-n)
V(FD) [V]	520	220	75	95
Resitivity	1.9 k Ω cm	1.4 k Ω cm	13 k Ω cm	3.3 k Ω cm
Orientation	<100>	<100>	<100>	<100>

n-on-n, p-on-n, n-on-p, FZ and Mcz
Irradiations: Ljubljana, CERN, Karlsruhe, Los Alamos, BNL
Testing: Santa Cruz, Liverpool, Ljubljana, New Mexico, Syracuse

Final production stage (mainly MCz) being processed at Micron for delivery in December

High Impact Common Project:

- several conclusive results on FZ vs. MCz, annealing, neutron vs. charged hadrons etc (reported at Vertex, PSD, IEEE, ATLAS Upgrade, P-type Workshops etc)
- ATLAS Upgrade p-type FZ strips run (ATLAS07) with HPK “fathered” by RD50 Common run
- ATLAS Upgrade “Planar Pixel Sensors” proposal directly spawned by RD50 common run

Extension of RD50 mask set to double-sided processing was approved by RD50
Discussion with Micron revealed that the time scale of fabrication would not match the availability of beams for irradiation next year.

Therefore I propose to not exercise this extension, but instead support at the same level the 4” double-sided run by Liverpool, since it will make many structures available on the December time scale. The groups involved in the extension proposal have been polled and have not objected.

Hartmut Sadrozinski